

## Photomask Japan 2014

### Best Paper Award Winners

Best Oral Presentations:

Program No.	Presentation Title	Name	Affiliation
4-3 [EMLC]	High performance mask fabrication process for the next-generation mask production	K. Yagawa, K. Ugajin, M. Suenaga, Y. Kobayashi, T. Motokawa, K. Hagihara, M. Saito, M. Itoh	Toshiba Corp., Japan
9-2 [BACUS]	In-Die Registration Measurement Using Novel Model-Based Approach for Advanced Technology Masks	S. Sato(1), F. Laske(2), S. Kunitani(1), T. Kamibayashi(1), A. Fuse(1), N. Takahashi(1), K.-D. Roeth(2), S. Czerkas(2), M. Daneshpanah(3), Y. Nagaoka(4)	(1)Toppan Printing Co., Ltd., Japan, (2)KLA-Tencor GmbH, Germany, (3)KLA-Tencor Corporation, USA, (4)KLA-Tencor Japan Ltd., Japan

Best Poster Presentation:

7d-2	Application of EB repair for high durable MoSi phase shift mask	S. Kanamitsu, K. Morishita, T. Hirano	Toshiba Corporation, Japan
------	---	---------------------------------------	----------------------------

Best Academic Poster Presentation:

7s-8	Electron beam current dependence on a surface potential distribution at a resist film on a conductive substrate	K. Kumagai, S. Hosoi, Y. Handa, M. Kotera	Major in Electrical and Electronic Engineering, Osaka Institute of Technology, Japan
------	---	---	--